



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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H 7316
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In re Application of:

Ko et al.

Serial No.: 09/711,324

Filed: November 13, 2000

For: ETCHANT WITH SELECTIVITY FOR
DOPED SILICON DIOXIDE OVER
UNDOPED SILICON DIOXIDE AND
SILICON NITRIDE, PROCESSES WHICH
EMPLOY THE ETCHANT, AND
STRUCTURES FORMED THEREBY

Examiner: K. Chen

Group Art Unit: 1765

Attorney Docket No.: 3526.4US
(97-1136.4)

CERTIFICATE OF MAILING

I hereby certify that this correspondence along with any attachments referred to or identified as being attached or enclosed is being deposited with the United States Postal Service as First Class Mail (under 37 C.F.R. § 1.8(a)) on the date of deposit shown below with sufficient postage and in an envelope addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231.

September 4, 2001
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Deidra Pfeil
Typed printed name of person whose signature is contained above

AMENDMENT UNDER 37 C.F.R. §1.116

Box AF
Commissioner for Patents
Washington, D.C. 20231

Sir:

The following amendments and remarks are filed in response to the remarks presented in the Final Office Action mailed July 3, 2001, the three-month shortened statutory period for response to which expires on October 3, 2001. As Monday, September 3, 2001, falls on the Labor Day holiday, this response is submitted on or before two months from the mailing date of the Final Office Action. 37 C.F.R. § 1.7.